2024년 1월 26일(금), 09:00-10:45
Room I(203),2층

D. Thin Film Process Technology 분과

[FI1-D] Atomic Layer Deposition - I

좌장: 엄태용 선임(한국화학연구원), 송봉근 교수(홍익대학교)

초청발표 FI1-D-1 09:00-09:30	Pt Thin Films by Atomic Layer Deposition Using Dimethyl(N,N-Dimethyl-3-Buten-1-Amine-N) Platinum and O_2 Reactant towards Semiconductor Application Woo-Jae Lee [1]Department of Nanotechnology Engineering, Pukyong National University
FI1-D-2 09:30-09:45	Growth of Rutile c-axis Oriented TiO_2 Thin-films with Ultralow Equivalent Oxide Thickness and Leakage Currents Taikyu Kim[1], Jihoon Jeon[1,2], Myungsu Jang[1,2], and Seong Keun Kim[1,2] [1]Electronic Materials Research Center, KIST, [2]KU-KIST Graduate School of Converging Science and Technology, Korea University
FI1-D-3 09:45-10:00	Improving Performance of $TiO_2/ZrO_2/TiO_2$ Laminated Capacitor by Layer-by-layer Phase Control Using Atomic Layer Annealing Geongu Han[1], Kyoungjae Ju[2], Chanwook Choi[2], Hyong June Kim[3], and Jihwan An[2,3] [1]Department of Manufacturing Systems and Design Engineering, Seoul National University of Science and Technology, [2]Department of Mechanical Engineering, POSTECH, [3]Institute of Energy and Environment, Seoul National University of Science and Technology
FI1-D-4 10:00-10:15	The Effect of Process Pressure on Improving Resistivity of Ru Thin Films Deposited by Atomic Layer Deposition Na-Gyeong Kang, Min-Ji Ha, and Ji-Hoon Ahn Department of Materials Science and Chemical Engineering, Hanyang University
FI1-D-5 10:15-10:30	Thermal Atomic Layer Deposition of Ru-incorporated MoCx Films as Cu Diffusion Barrier and Seed Layer Ji Sang Ahn and Jeong Hwan Han Department of Materials Science and Engineering, Seoul National University of Science and Technology

FI1-D-6 10:30-10:40	MoO_2 Film Fabrication via Atomic Layer Deposition with Mo(IV) Precursor and Oxygen and Ozone Reactants for DRAM Applications Ara Yoon, Hae Lin Yang, Sanghoon Lee, and Jin-Seong Park Division of Materials Science and Engineering, Hanyang University